

UNITED STATES PATENT AND TRADEMARK OFFICE
CERTIFICATE OF CORRECTION

PATENT NO. : 6,890,853 B2
APPLICATION NO. : 09/841800
DATED : May 10, 2005
INVENTOR(S) : Maximillian A. Biberger et al.

Page 1 of 2

It is certified that error appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

On the title page, item [56] add the following references:

--4,592,306	06/03/86	Gallego	118	719
4,670,126	06/02/87	Messer et al.	204	298
4,825,808	05/02/89	Takahashi et al.	118	719
4,951,601	08/28/90	Maydan et al.	118	719
5,934,856	08/10/99	Asakawa et al.	414	217
6,077,321	06/30/00	Adachi et al.	29	25.01
EP 0 244 951 A2	11/11/87	EP H 01 L	21/00	
EP 0 272 141 A2	06/22/88	EP H 01 L	21/00	
GB 2 193 482 A	02/10/88	GB B 25 J	18/02	
JP 10-144757	05/29/98	JP H 01 L	21/68	
JP 56-142629	11/07/81	JP H 01 L	21/205	
JP 60-238479	11/27/85	JP C 23 C	14/56	
JP 60-246635	12/06/85	JP H 01 L	21/302	
JP 61-231166	10/15/86	JP C 23 C	14/24	
JP 63-303059	12/09/88	JP C 23 C	14/22	

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WO 87/07309	12/03/87	WO	C 23 C	16/00
WO 91/12629	08/22/91	WO	H 01 L	21/00
WO 99/18603	04/15/99	WO	H 01 L	21/00

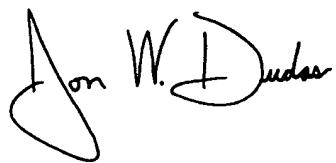
Hideaki Itakura et al., "Multi-Chamber Dry Etching System", Solid State Technology,
April 1982, pp. 209-214--.

Column 1, line 13, replace "deposition of film" with --deposition of films--.

Column 8: In Claim 13, replace "2,6-dimethylheptane-3,5-dione" with
--2,6-dimethylheptane-3,5-dione--.

Signed and Sealed this

Seventeenth Day of October, 2006



JON W. DUDAS
Director of the United States Patent and Trademark Office